

ABSTRACT

Accurate coating and developing having high intrasurface uniformity is achieved by suppressing the influence of components of a resist that may be eluted while a substrate coated with the resist is processed by immersion exposure. A coating unit coats a surface of a substrate with a resist. then, a first cleaning means including a cleaning nozzle cleans the substrate and then the substrate is subjected to an exposure process. Since only a small amount of components of the resist dissolves in a transparent liquid layer formed on the substrate for exposure, an exposure process can form lines in accurate line-widths. Consequently, a resist pattern of lines having accurate line-widths having high intrasurface uniformity can be formed on the substrate by developing the exposed resist.